IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

SHIMAZU et al

Serial No .:

Filed:

January 22, 2004

For:

Semiconductor Device And Its Production Process

REAFFIRMATION OF CLAIM FOR PRIORITY

Mail Stop: Application
Commissioner for Patents

January 22, 2004

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Under the provisions of 35 USC §119 and 37 CFR §1.55, Applicants hereby claim the right of priority based on Japanese Patent Application No. Japanese Application No. 10-267695, filed in Japan on September 22, 1998.

The certified copy of the above-referred to Japanese Patent Application was received by the International Bureau in prior application Serial No. 09/787,743, filed June 8, 2001.

Respectfully submitted,

Alan E. Schiavelli

Registration No. 32,087

ANTONELLI, TERRY, STOUT & KRAUS, LLP

AES/jla (703) 312-6600 (Rev. 4/92)

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EXAMINER INITIAL	DOCU	MENT N	JMBER					DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
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FOREIGN PATENT DOCUMENTS

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

 Mo et al "Formation and Properties of Ternary Silicide (CoNi)Si2 Thin Films, IEEE 1998 5th International Conference on Solid State And Integrated Circuit Technology pp 271-274
 Hong et al "Magneto-Optic Kerr Effect Measurements on FeCoSi Epitaxially Stabilized on Si (111), Journal of Magnetism and Magnetic Materials, vol. 165 pp 212-215
http://www.puretechnic.com and http://tosohsmd.com/tsprod.tspcobdt.htm, Material Data Sheet MDS 27.000 which includes the total metallics of the cobalt target, pp 1-4 and 1-3

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 Physical Review Letters, Vol. 78, No. 16 (April 1997) pp 3133-3136; full text
 Handbook on Thin Filter Manufacturing Method, Japan, Kyoritsu Shuppan KK (10/94) pp 321-322. "A Metal Silicide"
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		Safety and Health Guide For The Microelectronics Industry, Hazard Communication, OSHA 310, pp 9, 1998											310,		
			 												
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